What is claimed is:

1. A monolithic multi-focal length refractive element comprising:

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a single monolithic optical element blank comprising:

a first surface region having a first characteristic radius of curvature;

and

a second surface region having a second characteristic radius of

curvature.

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- 2. The monolithic multi-focal length refractive element as recited in Claim 1, wherein the value of an optical property for said first surface region is different from a value of said optical property for said second surface region.
- 15 3. The monolithic multi-focal length refractive element as recited in Claim 2 wherein said optical element blank comprises silica (SiO₂).
 - 4. The monolithic multi-focal length refractive element as recited in Claim 2 wherein said optical element blank comprises gallium arsenide (GaAs).

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5. The monolithic multi-focal length refractive element as recited in Claim

1 wherein said monolithic multi-focal length refractive element has a maximum dimension of less than five millimeters.

- The monolithic multi-focal length refractive element as recited in Claim
 1, wherein said monolithic optical element blank comprises a third surface region
 having a third characteristic radius of curvature.
 - 7. A method for making a multi-focal length refractive element, said method comprising:
- forming in an optical element blank a first surface region characterized by a first radius of curvature;

forming on said optical element blank a second surface region characterized by a second radius of curvature.

- 15 8. The method as recited in Claim 7 wherein said forming said first surface region comprises etching said optical element blank using a first etch process having a first etch selectivity.
- 9. The method as recited in Claim 8 wherein said forming said second
 20 surface region comprises etching said optical element blank using a second etch
 process having a second etch selectivity.

- 10. The method as recited in Claim 9 wherein said first etch selectivity is less than said second etch selectivity.
- The method as recited in Claim 7 additionally comprising forming a
 first shape transfer mask and etching said first shape transfer mask using a first etch process.
 - 12. The method as recited in Claim 11 additionally comprising etching said first shape transfer mask using a second etch process.
- 10 13. The method as recited in Claim 13 additionally comprising forming a second shape transfer mask.
 - 14. The method as recited in Claim 13 additionally comprising using a second etch process to etch said second shape transfer mask.

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15. A method for fabricating a multi-focal length refractive lens, said method comprising:

forming a mask element on a surface of an optical element blank;

heating said mask element to flow said mask element into a shape transfer

20 mask;

transferring the shape of said shape transfer mask to said optical element blank

by using a first etch process and a second etch process, wherein an etch selectivity of said first etch process is different from an etch selectivity of said second etch process.

- 16. The method as recited in Claim 15 wherein said mask element5 comprises an organic polymer material.
 - 17. The method as recited in Claim 15 wherein said mask element comprises a photosensitive material.
- 18. The method as recited in Claim 15 wherein said optical element blank comprises silica (SiO₂).
 - 19. The method as recited in Claim 15 wherein said optical element blank comprises gallium arsenide (GaAs).
- 15 20. The method as recited in Claim 15 wherein said mask element comprises photoresist.
 - 21. The method as recited in Claim 15 wherein said first etch selectivity is less than said second etch selectivity.

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- 22. The method as recited in Claim 15 wherein said etching comprises dry chemical etching.
- 23. The method as recited in Claim 15 additionally comprising forming said mask element using photolithography.